

INTERACTION OF NITROUS OXIDE WITH SINGLE
CRYSTAL SURFACES OF Cu (100) AND Cu (111)

BY

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تتضمن الدراسة استخدام تقنية الـ PES و LEED في جهاز واحد . أن خلاصتنا
 Cu(100) و Cu(111) لم يمتصا N_2O عند درجة حرارة الغرفة أن التحلل الانتقائي على
 السطحين عند تفاعل $N_2O(ads) \rightarrow N_2(g) + O(ads)$.
 تكونت ثلاثة أسطح على Cu(100) هي: $(\sqrt{2} \times \sqrt{2}) R 45^\circ - 0^\circ$ عند تسخين
 عند درجة حرارة الغرفة ، $(\sqrt{2} \times 2\sqrt{2}) R 45^\circ - 0^\circ$ عند تسخين
 البلورات إلى 800 K في N_2O ، وتركيب بعد ثلاث هزات $(\sqrt{2} \times \sqrt{2}) R 45^\circ - 0^\circ$
 حيث لم يمتص N_2O صحيح نوعه بل يمتص بالامتصاصات وتتكون نتيجة التداخل الحراري مع
 التحلل . أن امتصاص N_2O على سطح Cu (111) عند درجة حرارة الغرفة لم يغير التركيب
 الأصلي (1x1) للنحاس (111) Cu امتص N_2O جزئياً في 77 K . والجزئيات المتحصلة
 تحللت بعد تركها للسطح في الفراغ وتسخينها إلى درجة حرارة الغرفة

This study was carried out using a combination of PES and LEED techniques in one instrument. Both Cu(100) and Cu(111) surfaces did not show high tendency to adsorb N_2O at room temperature. Dissociative adsorption was found to occur on the two surfaces: $N_2O(ads) \rightarrow N_2(g) + O(ads)$.

Three surface structures were developed on Cu(100): $(\sqrt{2} \times \sqrt{2})$ R45°-O at room temperature; $(\sqrt{2} \times 2\sqrt{2})$ R45°-O after heating the crystal at 800 K in N₂O and a complex structure denoted as $(\sqrt{2} \times \underline{a})$ R45°-O, where \underline{a} is not integrally related to copper lattice parameter, as a result of the interaction with thermally dissociated N₂O. N₂O adsorption on Cu(111) surface at room temperature did not change the primitive (1 x 1) structure of Cu(111) surface. N₂O was molecularly adsorbed at 77 K. The adsorbed molecules were dissociated as a consequence of leaving the adsorbed phase in vacuum or during warming from 77 K to room temperature.

INTRODUCTION

The study of metal oxidation is important and interesting for both academic and technological purposes. Oxygen interaction with single crystal surfaces of copper has been extensively studied using modern techniques in surface chemistry. Despite some disagreement in the published data of oxygen interaction with copper single crystal surfaces, an intense information is available (1 - 34).

It is aimed in the present study to investigate the problem of interaction and/or oxidation of Cu(100) and Cu(111) single crystal surfaces by nitrous oxide. Such a study has received little attention in the literature (19, 35). The relatively low N-O bond energy in N₂O (163 kJ mole⁻¹) as compared to that in NO might suggest a possible dissociation of the molecule upon adsorption, particularly, at high temperatures. The published data of metal films oxidation by nitrous oxide showed similarity when N₂O or oxygen is used in the oxidation process (36, 37).

A combination of photoelectron spectroscopic study (XPS and UPS) and low energy electron diffraction (LEED) were employed in this investigation.

S. A. Isa and M. H. Matloob

EXPERIMENTAL

The apparatus used in a UHV stainless steel system built by Vacuum Generators Ltd. A pressure of 6×10^{-11} torr can be obtained after bakeout at 450 K for 10 hrs. The techniques of XPS, UPS and LEED are incorporated in one instrument which enable us to perform analytical, chemical and surface structural studies. A schematic diagram of the apparatus is shown in Fig. 1. The X-ray source is a twin Al K_{α} /Mg K_{α} and the UV light source is a helium dc discharge lamp which produces both HeI and HeII resonance lines at 21.21 and 40.8 eV respectively. The LEED optics involves retarding potential grids mounted close in front of a fluorescent screen maintained at a positive potential (7 kV) where bright spots of diffraction patterns can be observed through a glass window in the UHV chamber. Cu(100) and Cu(111) single crystals were obtained from Metals Research Ltd; a slice of 1 mm thickness of each crystal was cut by a spark erosion machine. The crystals, prior to insertion into the chamber, were planed and chemically polished (38). Cleaning of the crystals was performed by following the procedure of simultaneous heating and argon ion bombardment (800 eV and 2 μ A). The crystals were thereafter annealed at 450 K and finally examined by XPS for surface cleanliness before starting experiments. The specimens could be resistively heated up to \sim 820 K or cooled down to liquid nitrogen temperature. The gases used were spectroscopically pure and obtained from BOC.

RESULTS

A. Adsorption on Cu(100)

The interaction of N_2O with Cu(100) surface was examined in the temperature range 295 - 800 K. Molecular and thermally dissociated N_2O

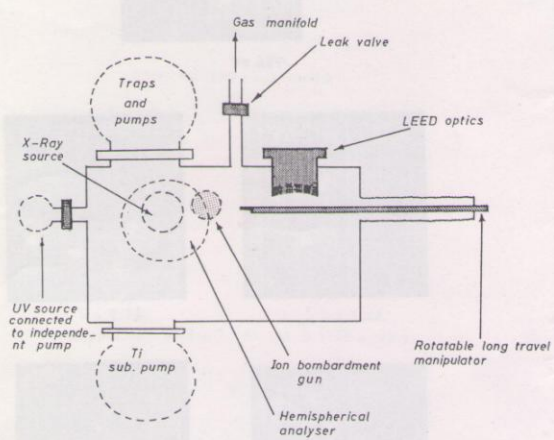


Fig. (1) The combination of LEED-XPS-UPS (ESCA 4).

S. A. Isa and M. H. Matloob

were used in this study. The clean Cu(100) surface (as shown by XPS) did not tend to adsorb N_2O in low exposures at room temperature. As a result of exposing the crystal to 1500 L of the gas at 295 K, diffraction patterns of $(\sqrt{2} \times \sqrt{2}) R45^\circ$ mesh were observed. XPS results showed an oxygen uptake of 0.55×10^{15} adsorbed species/cm² but no nitrogen was retained by the surface. The O1s binding energy was 530.1 eV with FWHM = 2.4 eV. A second surface structure, $(\sqrt{2} \times 2\sqrt{2}) R45^\circ$ appeared after exposing the clean surface to 2000 L of N_2O at 800 K then cooling the crystal to room temperature in an atmosphere of N_2O . The oxygen uptake was 0.74×10^{15} adsorbed species/cm² with O1s binding energy = 530.5 eV and FWHM = 2.5 eV. Identical surface

⊙ The concentration of the adsorbed species mentioned above was estimated on the basis of the following modified equation (39, 40) after smoothing the data and removing the background:

$$Y_m / Y_n = \mu_m N \sigma / \mu_n N n t \cos \theta$$

σ = surface concentration;

Y_m = photoelectron yield from the adlayer, i.e., either the O1s or N1s peaks;

Y_n = the intensity of the clean Cu 2P 3/2 peak;

N = Avogadro's number;

μ_n = ionization cross section for Cu 2P 3/2;

μ_m = ionization cross section for the O1s or N1s orbitals;

t = electron attenuation length in the Cu substrate;

p = density of copper;

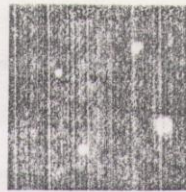
M = molecular weight of substrate;

θ = angle between collected electrons and the normal to substrate (45°).

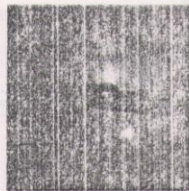
structures were developed when Cu(100) is exposed to oxygen at room temperature as shown in Fig.2 (41). The third stage of N_2O interaction with the Cu(100) surface was the use of thermally dissociated N_2O . Dissociated gas molecules were prepared by circulating N_2O at a pressure of 1×10^{-6} torr over a heated tungsten filament. The crystal was mounted facing the filament (at 800 K) and exposed to N_2O for 30 minutes. The crystal was then cooled down to room temperature in N_2O and examined by LEED and XPS. The diffraction patterns were quite different from those noticed previously; they were complex but well ordered and contained many extra spots along the edges of the $(\sqrt{2} \times 2\sqrt{2})R45^\circ$ mesh. Very similar diffraction patterns were noticed after heating the crystal in oxygen at temperatures $\gg 373$ K (41). Fig.3 shows typical examples of these patterns at a range of electron beam energy. The fractional extra spots were found to move along the edges of the $(\sqrt{2} \times 2\sqrt{2})R45^\circ$ mesh with changing the beam energy. The movement was neither towards the 00 spot nor to any other fixed direction. The complex surface structure was examined and found to be stable even after heating the crystal in vacuum at 800 K. The oxygen uptake was 1.5×10^{15} adsorbed species/cm² with O1s binding energy = 530.7 eV and FWHM = 2.4 eV. These values are also identical to those reported previously (41).

B. Adsorption on Cu(111)

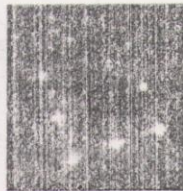
The clean Cu(111) surface, as examined by XPS, was exposed to nitrous oxide at room temperature. Initially, no N_2O adsorption occurred upon exposing the crystal to 800 L of the gas. Increasing the exposure to 1800 L resulted in a weak O1s peak at 530.1 eV but no sign of N1s peak was noticed in the spectrum. Further exposure to 4500 L of N_2O did not lead to a significant change in the spectra (Fig.4). The surface concentration of the adsorbed species was only 0.14×10^{15} per cm². Our LEED results showed the absence of any extra spots. The primitive structure of Cu(111)-(1 x 1) was only seen. This result confirms the



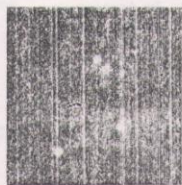
78.6 eV
Clean Cu(100) Surface



32.3 eV
($\sqrt{2} \times \sqrt{2}$) R-45-O Surface Structure



61.2 eV



31.2 eV
($\sqrt{2} \times \sqrt{2}$) R-45-O Surface Structure

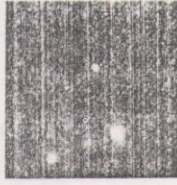
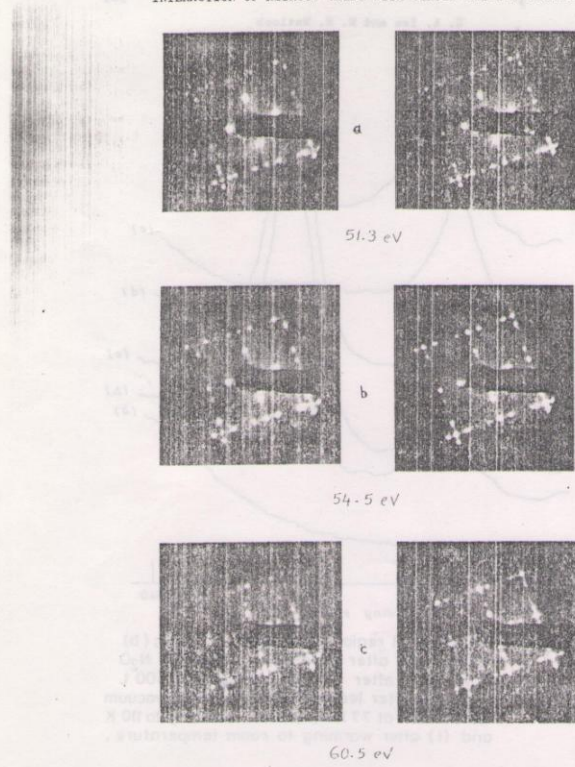


FIG. 2

FIG.3. The Complex Structure of $(\sqrt{2} \times a)R-45-O$

S. A. Isa and M. H. Matloob

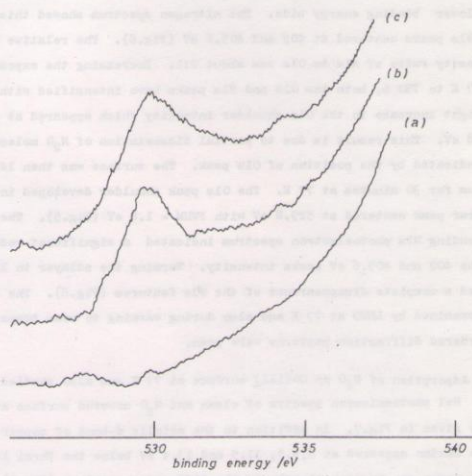


Fig. (4) O1s spectral region at 298 K for (a) clean Cu(III) surface; (b) and (c) the surface after exposure to 1800 L and 4500 L of N₂O.

published work of Ertl (19) who did not see extra spots in LEED patterns during N_2O adsorption on Cu(111) surface at room temperature.

The interaction of N_2O with Cu(111) surface was also studied at low temperatures to investigate whether there is dissociative adsorption or not. The clean Cu(111) surface was exposed to 150 L of N_2O at 77 K. A single O1s peak emerged at 535.4 eV (Fig.5) with a broad shoulder at the lower binding energy side. The nitrogen spectrum showed this time two N1s peaks centered at 402 and 405.6 eV (Fig.6). The relative peak intensity ratio of N1s to O1s was about 2:1. Increasing the exposure at 77 K to 750 L, both the O1s and N1s peaks have intensified with a slight increase in the O1s shoulder intensity which appeared at about 529.8 eV. This result is due to partial dissociation of N_2O molecules as indicated by the position of O1s peak. The surface was then left in vacuum for 30 minutes at 77 K. The O1s peak shoulder developed into a clear peak centered at 529.8 eV with FWHM = 1.8 eV (Fig.5). The corresponding N1s photoelectron spectrum indicated a significant reduction in the 402 and 405.6 eV peaks intensity. Warming the adlayer to 110 K caused a complete disappearance of the N1s features (Fig.6). The surface was examined by LEED at 77 K and also during warming to room temperature. No ordered diffraction patterns were seen.

Adsorption of N_2O on Cu(111) surface at 77 K was also studied by UPS. HeI photoemission spectra of clean and N_2O covered surface at 77 K are given in Fig.7. In addition to the metallic d-band of copper, four extra maxima appeared at 6.9, 9.5, 11.5 and 13.4 eV below the Fermi level. These peaks can be seen clearly in the difference spectrum (Fig.7). Within the range of the d-band an enhanced emission at 1.8 eV and a marked decrease in the d-band intensity were observed. The published results of N_2O adsorption on Ni and Au films at 77 K (42,43) showed almost the same positions of the extra peaks observed in HeI spectrum (Table 1).

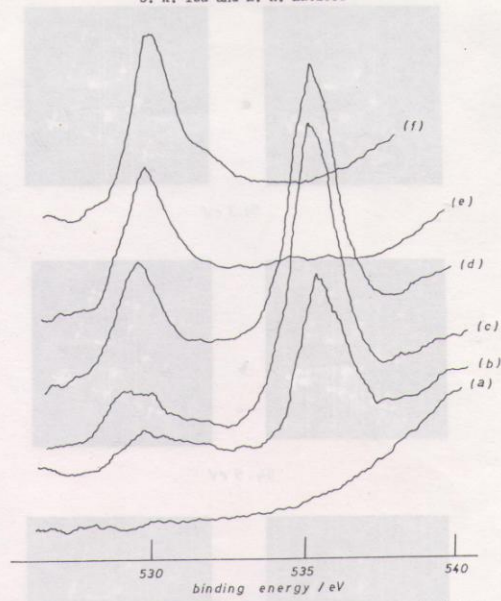


Fig. (5) O1s spectral region of (a) clean Cu(III); (b) the surface after exposure to 150 L of N₂O at 77 K; (c) after further exposure to 600 L N₂O; (d) after leaving the adlayer in vacuum for 30 min. at 77 K; (e) after warming to 110 K and (f) after warming to room temperature.

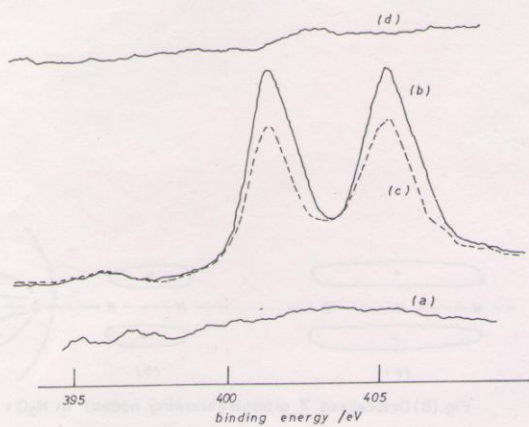


Fig.(6) N1s spectral region for (a) clean Cu(111) surface; (b) the surface after exposure to 750 L of N_2O at 77 K; (c) the adlayer (b) after leaving it in vacuum for 30 min. at 77 K and (d) the adlayer after warming to 110 K.

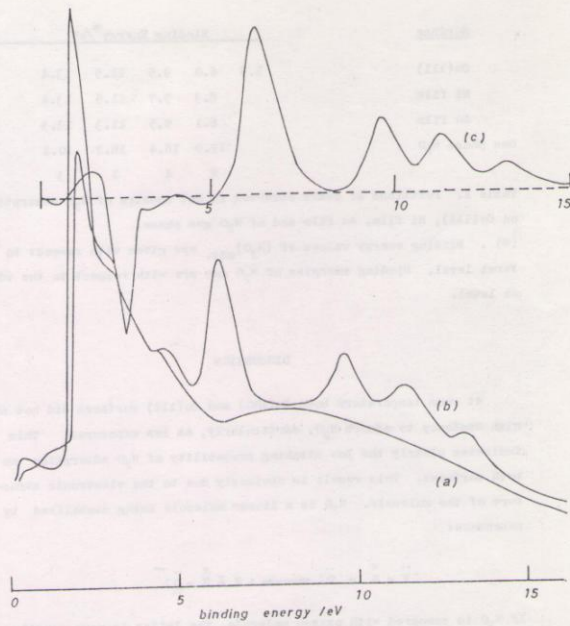


Fig. (7) He I spectra of (a) clean Cu(III) surface; (b) Cu(III) surface after exposure to 750 L of N₂O at 7 K and (c) the difference uv-spectra (b - a).

Surface	Binding Energy ^(a) /eV				
Cu(111)	1.8	6.0	9.5	11.5	13.4
Ni film		6.3	9.7	11.5	13.4
Au film		6.1	9.5	11.3	13.3
Gas phase N ₂ O		12.9	16.4	18.2	20.1
		2	4	1	3

Table 1. Positions of peaks observed in HeI spectra of N₂O adsorption on Cu(111), Ni film, Au film and of N₂O gas phase.

(a). Binding energy values of (N₂O) ads. are given with respect to the Fermi level. Binding energies of N₂O gas are with respect to the vacuum level.

DISCUSSION

At room temperature both Cu(100) and Cu(111) surfaces did not show high tendency to adsorb N₂O, particularly, at low exposures. This indicates clearly the low sticking probability of N₂O adsorption on both surfaces. This result is obviously due to the electronic structure of the molecule. N₂O is a linear molecule being stabilized by resonance:



If N₂O is compared with oxygen molecule, the latter is more reactive owing to its pseudo radical character caused by the presence of two unpaired electrons in different p levels. The electronic structure of N₂O molecule can be explained in terms of two σ bonds and two p pairs of non localized π orbitals extending over all three centers as shown in Fig. 8 (44). Each bond in the molecule will have a triple bond character which appears greater in the N-N link. This explains the ease of

S. A. Isa and M. H. Matloob

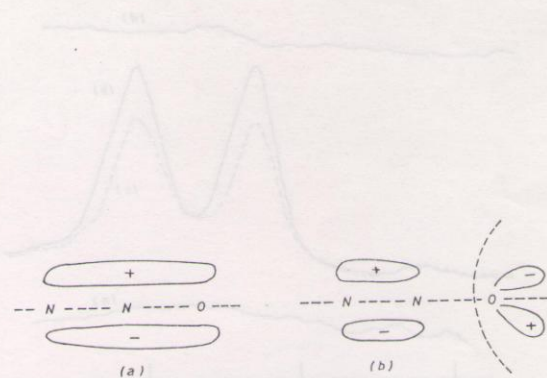
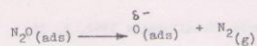


Fig. (8) Delocalized π orbitals (showing nodes) in N_2O :
 (a) bonding in both regions, N-N and N-O.
 (b) weakly bonding in N-N, weakly anti bonding in N-O.

N_2O dissociation through N-O bond and not the N-N bond. At high exposures of the gas at room temperature, the two surfaces adsorbed N_2O but Cu(100) was relatively more active than Cu(111). This result is expected due to the close packed structure of Cu(111) surface. It is evident from XPS results that N_2O adsorption on both surfaces at room temperature was dissociative (O1s peak at 530.2 eV and absence of any nitrogen species). This means that for each N_2O molecule adsorbed, one nitrogen molecule desorbed,



Adsorption of N_2O on Cu(111) surface did not change the primitive (1 x 1) structure while the adsorbed phase of Cu(100) showed a $(\sqrt{2} \times \sqrt{2})R45^\circ$ structure. The similarity in surface structures when N_2O or oxygen is used for adsorption on Cu(100) (41) supports the conclusion mentioned above of N_2O dissociative adsorption. The structure of $(\sqrt{2} \times \sqrt{2})R45^\circ$ was discussed in many publications of Cu(100) oxidation studies (23, 24, 45, 46). This structure was considered as a consequence of strongly adsorbed oxygen adatoms in four fold coordination on top of the unrestricted copper (100) surface (24). The structure of $(\sqrt{2} \times 2\sqrt{2})R45^\circ$ was observed by LEED after heating Cu(100) surface at 800 K in N_2O . This structure was also seen in oxygen adsorption with an exposure of 1000 L at room temperature (41). The transformation of surface structure from $(\sqrt{2} \times \sqrt{2})R45^\circ-O$ to $(\sqrt{2} \times \sqrt{2})R45^\circ-O$ was accompanied by an increase in the O1s binding energy of 0.4 eV which could be due to some oxygen incorporation into the metal lattice. Braithwaite et al (24) have suggested that surface reconstruction occurs only when the mesh changes to $(\sqrt{2} \times \sqrt{2})R45^\circ-O$.

The complex structure which emerged as a consequence of Cu(100)

S. A. Isa and M. H. Matloob

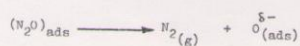
oxidation by thermally dissociated N_2O is suggested to be due to a coincidence lattice as a result of double diffraction. The dimensions of this structure are $Cu(100) - (\sqrt{2} \times a) R45^\circ - O$ where a is not integrally related to copper lattice parameter.

The N_2O adlayer on $Cu(100)$ surface showed by LEED - in all stages of N_2O adsorption - no evidence of formation of six fold symmetry which was noticed in two previous studies (19, 35).

Adsorption of N_2O on $Cu(111)$ surface at 77 K has shown two N1s peaks in X-ray photoelectron spectrum reflecting two non-equivalent nitrogen atoms in N_2O . This conclusion indicates the existence of the adsorbed N_2O in its molecular form. The relative intensity ratio of N1s to O1s (2:1) suggests also the molecular form of the adsorbed phase.

UPS data obtained at this stage confirm the XPS results. The compare UV induced spectra of the adsorbed phase with that of the gas phase, two factors have to be taken into consideration (47, 48). The first is the work function correction and the second is the relaxation effect. In our work, 5 eV as a work function correction and 2 eV for the relaxation effect have been added to match the spectra of the gaseous and adsorbed phases (42, 43, 49). In such a case we find N_2O adsorption at 77 K is mainly molecular.

The weak emission in the UV induced spectrum at 1.8 eV may be attributed to a d-band splitting which arises from the presence of small $O_{(ads)}^-$ concentration. The changes occurred in both XPS and UPS results as a consequence of leaving the adsorbed phase at 77 K in vacuum or warming to room temperature reflect $(N_2O)_{ads}$ dissociation:



It is interesting to note that the concentration of oxygen species formed at 77 K after leaving the adlayer in vacuum for 30 minutes was four times greater than that formed when Cu(111) surface is exposed to 1800 L of N_2O at room temperature. This result is unexpected since thermal energy should facilitate the dissociation process of N_2O . To understand such a behaviour, information concerning the geometry and the electronic state of N_2O species is required at 77 K. Within the frame work of our XPS and UPS data, such information can not be extracted. However, two points can possibly be considered; first, $N_2O(ads)$ species at 77 K play a precursor role for dissociation and second, due to low heat of N_2O adsorption (~ 30 k J mole $^{-1}$) a very low concentration of these precursors is formed at room temperature compared to that at 77 K. Similar observation was reported by Kishi and Roberts (50) upon N_2 adsorption on iron.

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